

Applicant(s): Hiroyuki UWAZUMI et al.
Atty. Docket No.: 32307-198189

IN THE TITLE:

Please replace the title with the following new title:

SPUTTERING TARGET FOR PRODUCTION OF A MAGNETIC RECORDING
MEDIUM

IN THE SPECIFICATION

Please delete the first paragraph on page 1, please add as the first paragraph on page 1 the following:

CROSS REFERENCE TO RELATED APPLICATIONS

This application is a divisional application of Application No. 09/789,928 filed February 22, 2001, which claims priority of the commonly owned Japanese application Serial No. 2000-046471 filed February 23, 2000. The disclosure of the above-referenced patent applications, as well as that of each US and foreign patent and patent application identified in the specification of the present application, is incorporated herein by reference.

Delete the paragraph at page 2, lines 12-21 and replace it with the following paragraph:

Examples using the granular magnetic layer are shown in Japanese patent Application Laid-open No. 8-255342 (1996) and U.S. Patent No. 5,679,473, Japanese Patent Application Laid-open No. 8-255342 (1996) proposed the achievement of a low noise by laminating a nonmagnetic film, a ferromagnetic film, and a nonmagnetic film sequentially and then heat treating the laminate to form a granular recording layer comprising ferromagnetic crystal grains dispersed in the nonmagnetic film. In this case, a silicon oxide or nitride is used as the nonmagnetic film.